

Title (en)

Positive type photoresist composition.

Title (de)

Positiv arbeitende Photoresistzusammensetzung.

Title (fr)

Composition de photorésist du type positif.

Publication

**EP 0471326 A1 19920219 (EN)**

Application

**EP 91113522 A 19910812**

Priority

JP 21373190 A 19900814

Abstract (en)

A positive type photoresist composition contains (a) 100 parts by weight of a resin which is a polymer compound (A) including carbon-carbon double bonds and having a molecular weight of 300 to 30,000 and an iodine value of 50 to 500. To at least a part of the double bonds of the polymer compound (A), a group represented by the formula (I) is introduced <CHEM> wherein R<1> denotes a hydrogen atom, a halogen atom or an alkyl group having 1 to 3 carbon atoms and R<2> denotes an alkyl group having 1 to 10 carbon atoms, a cycloalkyl group or an aryl group. The composition further contains (b) 25 to 100 parts by weight of a compound containing a quinone diazide unit.

IPC 1-7

**G03F 7/023**; **G03F 7/039**

IPC 8 full level

**C08F 8/46** (2006.01); **G03F 7/023** (2006.01); **H01L 21/027** (2006.01); **H01L 21/30** (2006.01); **H05K 3/00** (2006.01); **H05K 3/06** (2006.01)

CPC (source: EP US)

**G03F 7/0233** (2013.01 - EP US)

Citation (search report)

[A] EP 0095388 A2 19831130 - SUMITOMO CHEMICAL CO [JP]

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DE FR GB

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